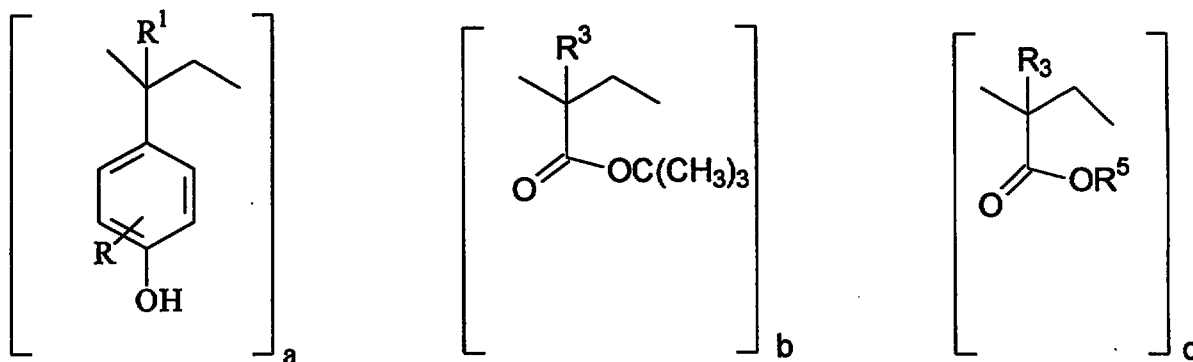


ABSTRACT OF THE DISCLOSURE

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A photosensitive resist composition comprising:

a polymer of *tertiary*-butyl acrylate having monomeric units of:



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where $0.5 \leq a \leq 0.7$; $0.15 \leq b \leq 0.3$; $0.1 \leq c \leq 0.2$; $0.3 < b + c \leq 0.5$; R is H, or a C₁-C₄ alkyl group; R¹ = H, methyl, CH₂OR²; each R³ is independently selected from H, methyl, CH₂OR, CH₂CN, CH₂X, or CH₂COOR⁴ group where X = Cl, I, Br, or F; R² is H, or C₁-C₄ alkyl; R⁴ is a C₁-C₄ alkyl group; R⁵ is f a isobornyl, cyclohexyl methyl, cyclohexyl ethyl, benzyl, phenethyl, or tetrahydrofurfural group

a photoacid generator;

a solvent; and

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optionally, a basic compound.

This Sheet Has Been Replaced

